

### **Amendments to the Claims**

1. (*Currently Amended*) A structure (~~10, 20~~) comprising at least one proportional variable resistor (~~24~~) suitable for electrically measuring unidirectional misalignment of stitched masks in etched interconnect layers, said structure comprising at least a first mask (~~10~~) and a second mask (~~20~~) that when superimposed comprise at least two test pads (~~14, 16~~) and interconnects (~~12, 22~~) the resistance between (~~24~~) which can be measured.

2. (*Original*) The invention according to claim 1 comprising at least one directly proportional variable resistor.

3. (*Original*) The invention according to claim 1 comprising at least one inversely proportional variable resistor.

4. (*Currently Amended*) The invention (~~30, 50~~) according to claim 1 comprising at least one stick type (~~32, 24, 36, 38~~) interconnect.

5. (*Currently Amended*) The invention according (~~60, 70~~) to claim 1 comprising at least one hook type interconnect (~~62, 72~~).

6. (*Original*) A system for electrically measuring unidirectional misalignment of stitched masks in etched interconnect layers, said system comprising at least one proportional variable resistor comprising a reference mask comprising at least two test pads and a second mask comprising at least one interconnect; and a probe for testing the resistance between said interconnect of said reference mask and said interconnect of said second mask when said masks are superimposed.

7. (*Original*) The invention according to claim 6, the at least one interconnect of said reference mask comprising at least one stick type interconnect.

8. (*Original*) The invention according to claim 6, the at least one interconnect of said reference mask comprising at least one hook type interconnect.

9. (*Original*) The invention according to claim 6, the at least one interconnect of said second mask comprising at least one stick type interconnect.

10. (*Original*) The invention according to claim 6, the at least one interconnect of said second mask comprising at least one hook type interconnect.

11. (*Original*) The invention according to claim 6, said system comprising at least one inversely proportional variable resistor.

12. (*Original*) The invention according to claim 6, said system comprising at least one directly proportional variable resistor.

13. (*Original*) A method of measuring stitched mask misalignment in etched interconnect layers comprising the steps of: providing a reference mask comprising at least two test pads; providing a second mask comprising at least one interconnect; superimposing said reference

mask and said second mask to provide at least one proportional variable resistor; electrically measuring the resistance of said at least one proportional variable resistor.

14. *(Original)* The method according to claim 13 further comprising the step of establishing an optimum resistance between said test pads.

15. *(Original)* The invention according to claim 14 comprising the further steps of comparing a measured resistance to said optimum resistance and adjusting the position of said masks to alignment.